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U.S. UTILITY Patent Application

D.I.P.E. SCANNED <i>2009 AC3</i> Q.A. <i>LA</i>	PATENT DATE
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APPLICATION NO. 09/729339	CONT/PRIOR F	CLASS 438	SUBCLASS 29	ART UNIT 2018	EXAMINER Q. HOANG
APPLICANTS Kyoichi Suwa					
TITLE Mask, exposure method, line width measuring method, and method for manufacturing semiconductor devices					

PTO-2040
12/99

ISSUING CLASSIFICATION									
ORIGINAL				CROSS REFERENCE(S)					
CLASS		SUBCLASS		CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)				
INTERNATIONAL CLASSIFICATION									

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	_____ (Assistant Examiner) (Date)			NOTICE OF ALLOWANCE MAILED _____	
	_____ (Primary Examiner) (Date)			ISSUE FEE Amount Due Date Paid	
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